

IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 2, line 3, with the following.

To the contrary, a multi-beam system for drawing a pattern simultaneously with a plurality of electron beams without using any mask has been proposed and is very advantageous to for practical use because of the absence of physical mask formation and exchange. What is important in using the multi-electron beams is the number of electron lenses formed in an array used in an electron optical system. The number of electron lenses determines the number of electron beams, and is a main factor which determines the throughput. Downsizing while improving the performance of the electron optical system array is one of the keys to improving the performance of the multi-beam exposure apparatus.

Please substitute the paragraph beginning at page 3, line 6, with the following.

In the electron optical system array disclosed in USP 4,419,580, Si substrates that are processed thin must be stacked. The fabrication process becomes difficult at a small electrode interval, and the multilayered structure is low in strength.